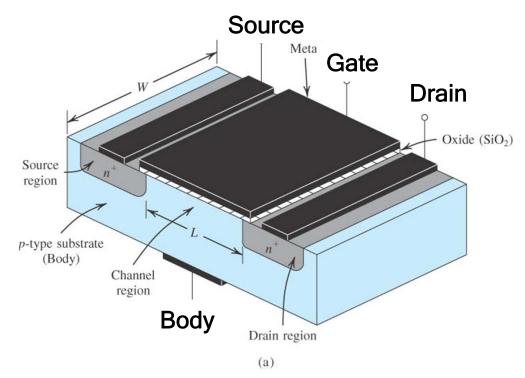
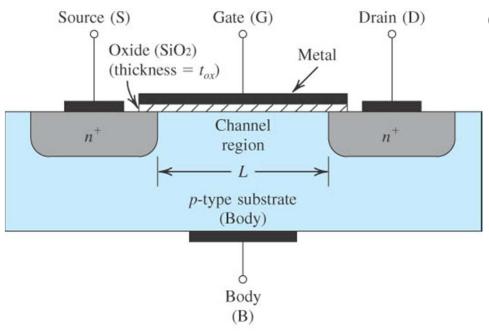
MOSFET: Metal Oxide Semiconductor Field Effect Transistor



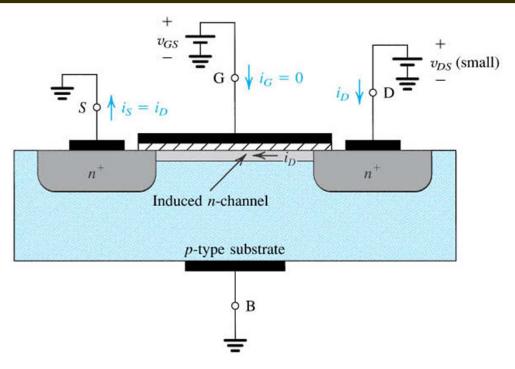
Control current flow between S and D with voltage applied at G NMOS, PMOS

NMOS: n-channel MOSFET



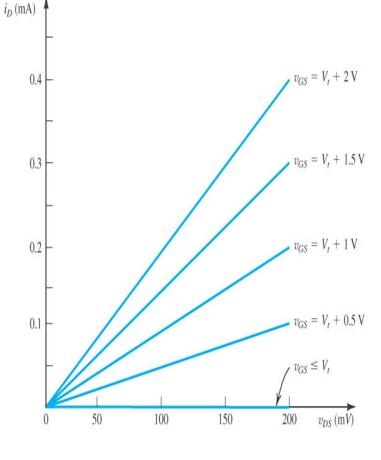
Can currents flow between S and D?

- → Need carriers (electrons)
- → Apply gate voltage (v_{GS} >V_T>0) (V_T: Threshold voltage)

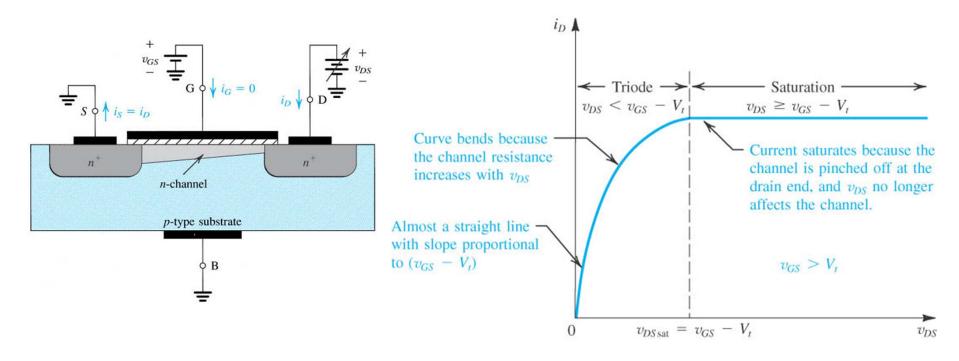


With $v_{GS}>v_T$ (threshold voltage), channel is formed. (Gate and p-substrate is acting as a capacitor) More carriers with higher v_{GS}

How does i_D change with v_{DS}?





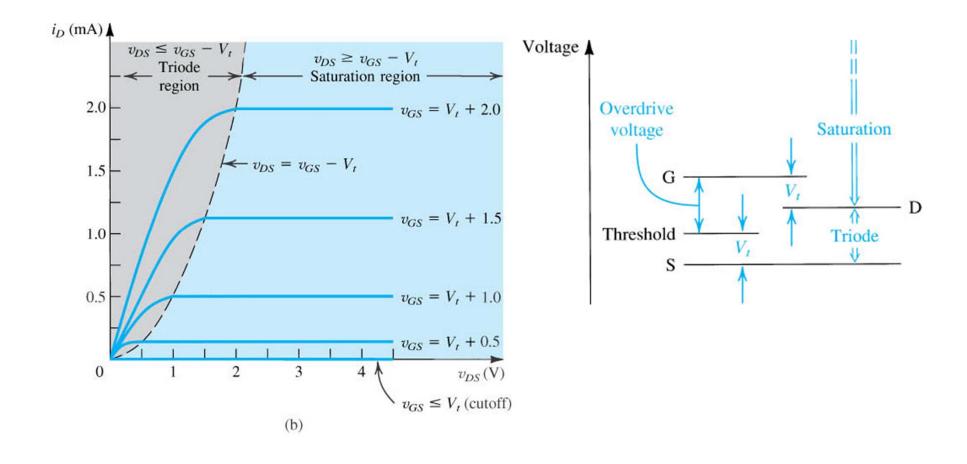


- With v_{DS} increase, i_D begins to saturate
- → Less carriers In Drain side (V_{GD}=V_{GS} + V_{SD}=V_{GS}-V_{DS})

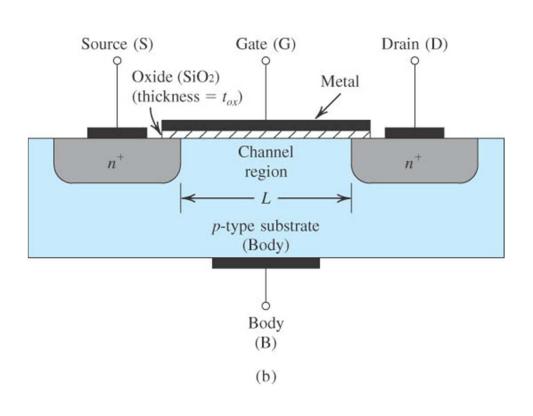
When $v_{DS} = v_{GS} - v_{T,} (v_{GD} = v_{T})$, channel is pinched off

→ No further increase in i_D

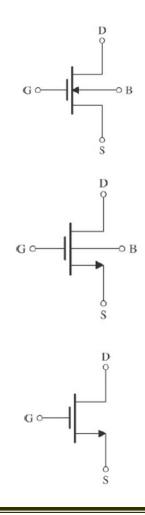
MOSFET (NMOS) I-V Characteristics

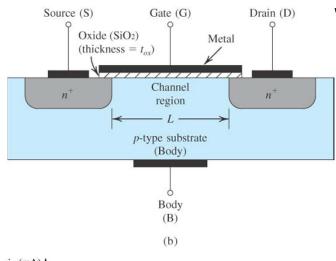


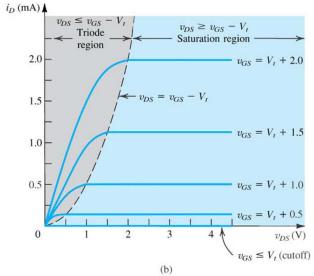
NMOS: n-channel MOSFET



Circuit Symbols







With more in-depth analyses,

In triode,
$$i_D = \mu_n C_{ox} \frac{W}{L} \left[(v_{GS} - V_t) \cdot v_{DS} - \frac{1}{2} v_{DS}^2 \right]$$

 $(v_{GS} > V_t \text{ and } v_{DS} \le v_{GS} - v_T)$

In saturation,
$$i_D = \frac{1}{2} \mu_n C_{ox} \frac{W}{L} (v_{GS} - V_t)^2$$

 $(v_{GS} > V_t \text{ and } v_{DS} \ge v_{GS} - v_T)$

 μ_n : electron mobility

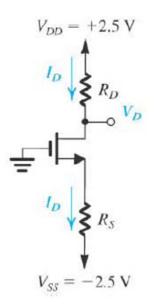
 C_{ox} : oxide capacitance

 V_t : threshold voltage

$$k' = \mu_n C_{ox}$$

Determine R_D and R_S so that I_D =0.4 mA and V_D =0.5V.

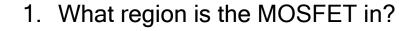
$$V_t = 0.7V$$
, $\mu_n C_{ox} (k') = 100 \mu A/V^2$, L= 1 μ m, W= 32 μ m

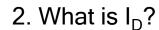


- 1. What region is the MOSFET in?
- 2. What is V_S?
- 3. R_D and R_S ?

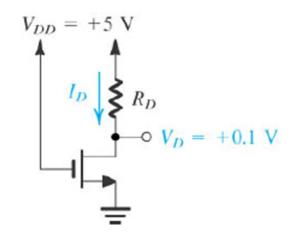
Determine R_D so that V_D = 0.1V.

$$V_t$$
= 1V, $\mu_n C_{ox} W/L$ = 1mA/V²





3. Whait is R_D ?



Homework: (Due Nov. 11)

Example 6.6, 6.7, 6.8 in Razavi